

As shown in Fig. 2(f), we can see that $n_{2\text{eff}}$ is negative and the value of $|n_{2\text{eff}}|$ increases from 2.50×10^{-13} to 1.70×10^{-12} cm^2/W as τ_p increases from 4.8 to 10.7 ns with the same pulse energy of 5.75 μJ ($F_0 = 2.54$ J/cm^2). As the pulse energy increases, the value of $|n_{2\text{eff}}|$ decreases. For example, the $|n_{2\text{eff}}|$ value decreases from 3.52×10^{-13} to 2.32×10^{-13} cm^2/W as input pulse energy from 1.90 μJ ($F_0 = 0.84$ J/cm^2) to 8.15 μJ ($F_0 = 3.60$ J/cm^2) with the same pulsewidth τ_p of 4.8 ns. Decreasing $|n_{2\text{eff}}|$ values with increasing input pulse energy indicates that the NLR responses are not arising from intrinsic third-order nonlinear optical response. This phenomenon was also studied in Ref. 30.

The NLR of nigrosine in DMF was also measured, we found that the NLR response and the value of $|n_{2\text{eff}}|$ for the dispersion of GO in DMF were comparable with that for the solution of nigrosine in DMF under the same condition. Since the NLR of nigrosine solution mainly originate from thermal effect [31] and no nonlinear optical signal for DMF was observed in our nanosecond experiments, so the strong pulsewidth influence on NLR indicates the thermal effect exists in the dispersion in nanosecond regime [32]. To further confirm the thermal origin of the NLR, we also measured the NLR of GO under the conditions of two different beam waist radius ω_0 of 12 μm and 22 μm with the same input fluence F_0 at focus. As shown in Figs. 3(a) and 3(b), when ω_0 changes from 12 μm to 22 μm , τ_{ac} increases from 8.3 to 15.3 ns. For $\tau_p = 10.7$ ns, the value of $|n_{2\text{eff}}|$ decreases from 2.26×10^{-12} cm^2/W ($\Delta T_{p-y} = 0.76$) to 8.80×10^{-13} cm^2/W ($\Delta T_{p-y} = 0.54$), with a decreased factor of 2.57 (the ratio of ΔT_{p-y} is 1.41), while for $\tau_p = 4.8$ ns, the value decreases from 2.5×10^{-14} cm^2/W ($\Delta T_{p-y} = 0.42$) to 1.3×10^{-14} cm^2/W ($\Delta T_{p-y} = 0.4$), with a decreased factor of 1.92 (1.05). So $|n_{2\text{eff}}|$ (or ΔT_{p-y}) decreases greatly for larger beam waist, which also indicates the existence of thermal effect [31].

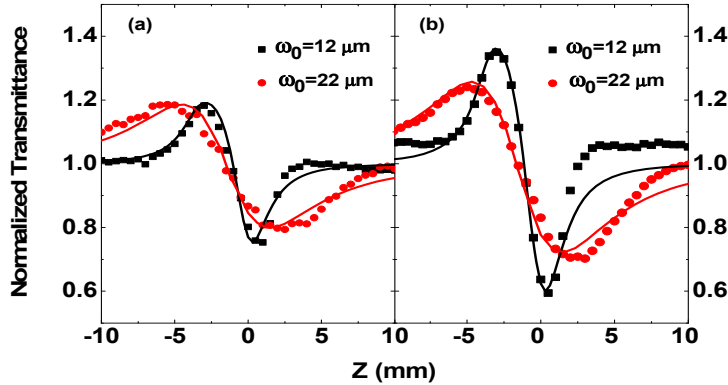


Fig. 3. NLR Z-scan curves of the dispersion of GO in DMF for two different beam waist radius ω_0 for $\tau_p = 4.8$ ns, $F_0 = 2.54$ J/cm^2 . (b) $\tau_p = 10.7$ ns, $F_0 = 1.22$ J/cm^2 . Solid lines are theoretical fits.

SA of the dispersion is attributed to band filling effect of sp^2 domains and RSA can be mainly arising from TPA of sp^3 matrix of GO sheets [7, 8, 12]. By fitting, I_s was obtained to be $\sim 10^7$ W/cm^2 , β_{eff} to be $3 \sim 11.5 \times 10^{-8}$ cm/W , as τ_p increases from 4.8 to 10.7 ns with the same pulse energy of 5.75 μJ ($F_0 = 2.54$ J/cm^2), while β_{eff} is near a constant as pulse energy increases with the same τ_p .

Since GO exhibited SA arising from the sp^2 domains, and RSA from the sp^3 matrix in nanosecond, picosecond and femtosecond regime, respectively [7–9, 12], NLR from π electrons and free carriers of sp^2 carbon domains, bound electrons and free carriers of sp^3 matrix may be involved, similar to the case in some semiconductors [33], so NLR response

from GO sheets should not be excluded. However, it is difficult to observe the NLR of GO sheets in nanosecond regime due to strong thermal effect.

To measure the intrinsic NLR of GO sheets, shorter pulses (35 ps) were used. For $\omega_0 = 16 \mu\text{m}$, $\tau_{\text{ac}} = 11.1\text{ns}$, $\tau_p/\tau_{\text{ac}} = 0.003$, thus thermal effect can be ignored for the 35 ps pulse. From Figs. 4(a) and 4(b) we can see that GO dispersion shows SA at lower intensity (9.0 GW/cm^2), with further increasing in the intensity, RSA takes place near focus. Since no NLA response of DMF was observed during the open-aperture Z-scan experiments, the SA and RSA behavior should be arising from GO sheets in the dispersion. The fits were obtained by using $I_s = 3.2 \text{ GW/cm}^2$ and $\beta_{\text{eff}} \sim 3.7 \times 10^{-10} \text{ cm/W}$.

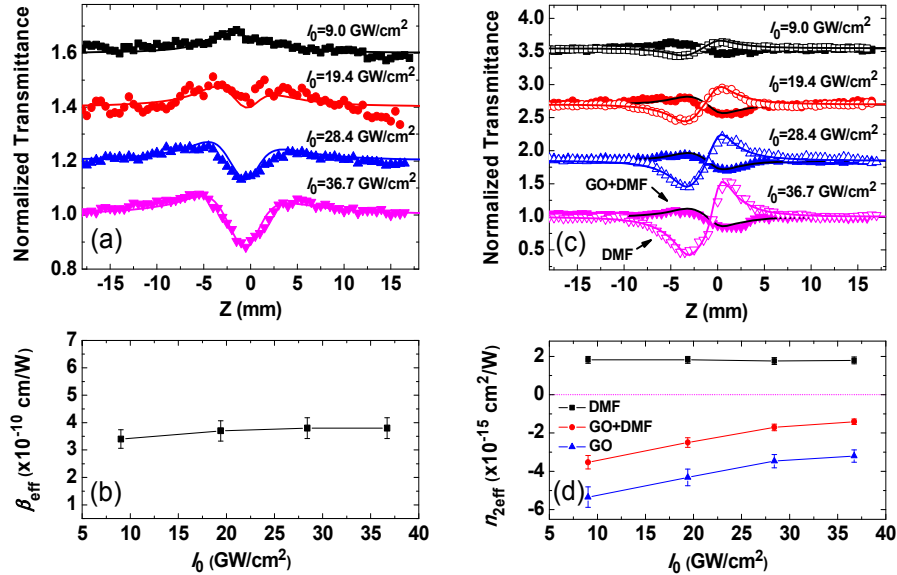


Fig. 4. For 35 ps pulse at 532nm: (a) Open-aperture Z-scan curves of the dispersion of GO in DMF (GO + DMF). (c) NLR Z-scan curves of the dispersion of GO in DMF (GO + DMF) and DMF, solid icons stand for the dispersion (GO + DMF), hollow icons stand for the solvent of DMF. Solid lines are theoretical fits. (b) Effective TPA coefficient β_{eff} of GO as a function of incident intensity. (d) Effective NLR coefficient $n_{2,\text{eff}}$ of DMF, the dispersion and GO sheets as functions of incident intensity.

For NLR experiments, the NLR properties of solvent DMF cannot be ignored due to the strong peak on-axis intensity I_0 in the sample under picosecond pulse, so the refraction index change Δn (dispersion) for the dispersion can be expressed as Δn (dispersion) = Δn (GO) + Δn (DMF), where Δn (GO) is the refraction index change of GO sheets and Δn (DMF) is that of the solvent DMF. Results show that DMF has an intensity-independent positive NLR coefficient n_2 of $1.8 \times 10^{-15} \text{ cm}^2/\text{W}$, while GO dispersion (GO + DMF) show negative NLR behaviors arising from GO sheets. As shown in Figs. 4(c) and 4(d), we found that $n_{2,\text{eff}}$ is negative and the value of $|n_{2,\text{eff}}|$ of dispersion decreases from $3.5 \times 10^{-15} \text{ cm}^2/\text{W}$ to $1.4 \times 10^{-15} \text{ cm}^2/\text{W}$, as the intensity increases from 9.0 GW/cm^2 to 36.7 GW/cm^2 . The value of $|n_{2,\text{eff}}|$ of GO sheets from calculation decreases from $5.3 \times 10^{-15} \text{ cm}^2/\text{W}$ to $3.2 \times 10^{-15} \text{ cm}^2/\text{W}$. Comparing the open-aperture Z-scan curves in Fig. 4(a) with NLR curves in Fig. 4(c), we note that GO dispersion (and then GO sheets) keeps the negative NLR behaviors though the SA behavior to RSA transition.

Figures 5(a) and 5(c) show the open-aperture Z-scan and NLR curves of the dispersion of GO in DMF under femtosecond pulse laser at 800 nm with different intensity. The results are

similar to the case of picosecond experiments although the laser wavelength and pulse width are different. GO dispersion exhibits SA at lower intensity (82.1 GW/cm^2), with further increase in the intensity, RSA occurs near focus. $I_S = 17.5 \text{ GW/cm}^2$ and β_{eff} was about $2.5 \times 10^{-11} \text{ cm/W}$ from fitting, as shown in Fig. 5(b). In Fig. 5(d) the results of fits show that DMF has an intensity-independent positive NLR coefficient n_2 of $6.3 \times 10^{-16} \text{ cm}^2/\text{W}$. There is a basic agreement with n_2 of DMF in Ref. 21 taking into account the NLR of the quartz cell. We also can see that GO dispersion (GO + DMF) keeps the negative NLR behaviors and the value of $|n_{2\text{eff}}|$ decreases from $5.3 \times 10^{-16} \text{ cm}^2/\text{W}$ to $4.3 \times 10^{-16} \text{ cm}^2/\text{W}$, the calculated value of $n_{2\text{eff}}$ of GO sheets nearly keeps a constant of $-1.1 \times 10^{-15} \text{ cm}^2/\text{W}$, as intensity increases from 82.1 GW/cm^2 to 224 GW/cm^2 . We also should note that GO dispersion (and then GO sheets) keeps the negative NLR behaviors though the SA behavior to RSA transition, similar to the case in picosecond time regime.

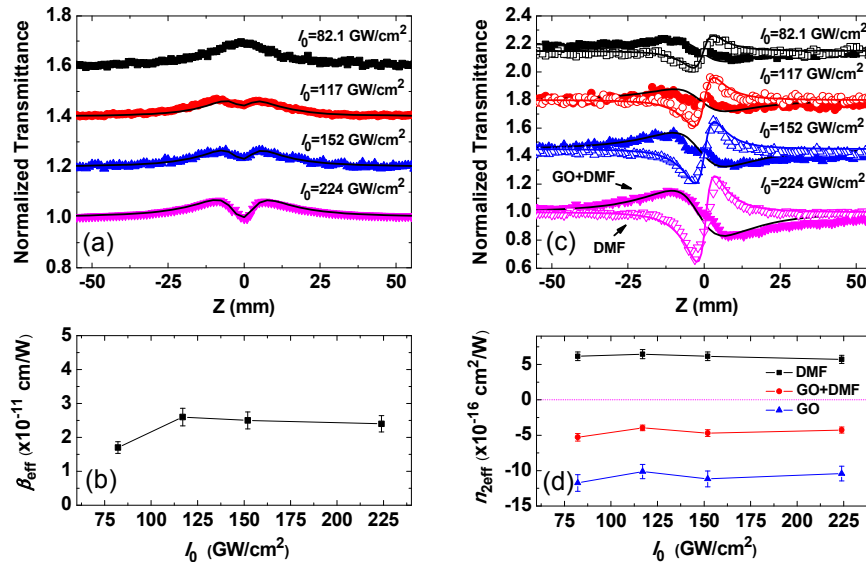


Fig. 5. For 120 fs pulse at 800 nm: (a) Open-aperture Z-scan curves of the dispersion of GO in DMF (GO + DMF). (c) NLR Z-scan curves of the dispersion of GO in DMF (GO + DMF) and DMF, solid icons stand for the dispersion (GO + DMF), hollow icons stand for the solvent of DMF. Solid lines are theoretical fits. (b) Effective TPA coefficient β_{eff} of GO as a function of incident intensity. (d) Effective NLR coefficient $n_{2\text{eff}}$ of DMF, the dispersion and GO sheets as functions of incident intensity.

In femtosecond time regime, electronic polarization, population redistribution (or excited states refraction), free carrier refraction would contribute to the NLR of GO sheets. However, there may be additional molecular reorientation contribution in picosecond and nanosecond time regime. For GO sheets, since the negative NLR were accompanied by SA and RSA in picosecond and femtosecond time regime, the mechanism of NLR from GO sheets can be explained by the schematic drawing shown in Fig. 6. As shown in Fig. 6, the sp^2 domain with a diameter of $\sim 3 \text{ nm}$, has an narrow energy gaps of $\sim 0.5 \text{ eV}$ [24,34–36], the optical absorption of electrons in sp^2 domains can be saturable easily and SA occur due to valence depletion and conduction band filling. Meanwhile, the π electrons and free carrier refraction in the conduction band of sp^2 domains may contribute to NLR properties.

For sp^3 matrix, the energy gaps are large (typically 2.7–3.1 eV) [37], when the intensity of laser pulse increases, the bound electrons in the valence band in sp^3 matrix will transit to conduction band and become free carriers through TPA mechanism for 532nm or 800 nm

pulse laser. Since the relaxation time of free carriers are in the order of hundreds of femtosecond, and a few picoseconds to scores of picoseconds [8], the bound electron NLR in the valence band and free carrier refraction in the conduction band of sp^3 matrix will also contribute to the NLR response of GO sheets. In GO sheets, sp^2 domains and sp^3 matrix are coexistence, so SA, TPA and possible free carrier absorption (FCA) are coexistence in a GO sheet. In femtosecond time regime, the NLR from π electrons, bound electrons in the valence band and free carriers in the conduction band will contribute to the NLR of the whole GO sheets. What' more, in the time regime of picosecond or longer, molecular reorientation effects of GO sheets may be also involved. While in nanosecond time regime, the contribution of these processes can be neglected because of the dominant transient thermal effect.

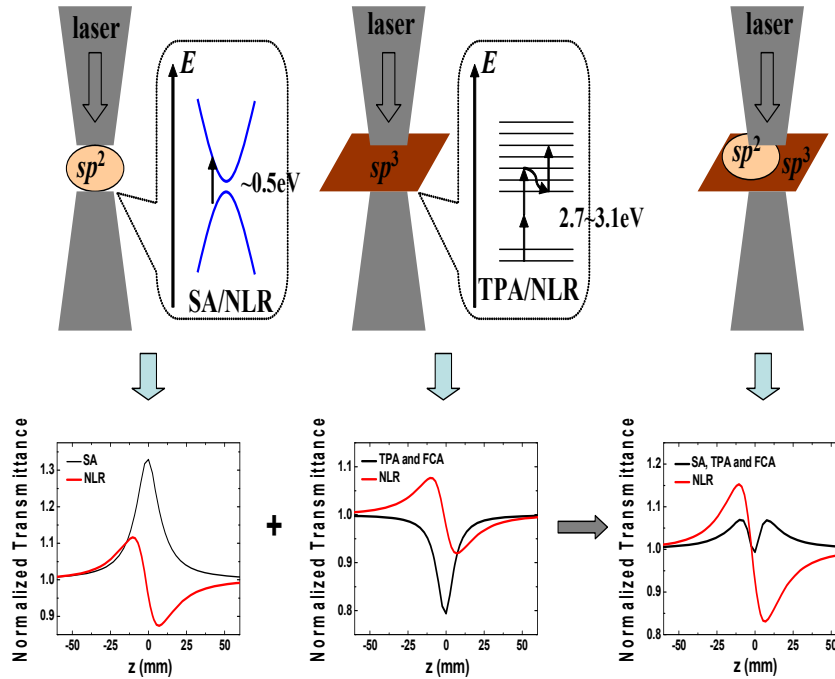


Fig. 6. A schematic drawing of NLA and NLR arising from sp^2 domains and sp^3 matrix of GO sheets.

It should be pointed out that there are many differences in NLR mechanisms between the graphene layer on a substrate, graphene sheets in solution dispersions and GO sheets in dispersions. For single layer or few-layer graphene on a substrate, the NLR from π electrons is dominant and NLR are not affected by cumulative thermal effect due to the very high thermal diffusion coefficient of graphene [15]. For graphene sheets in solution dispersions, both π electrons and the reorientation and alignment of the graphene sheets can contribute to the NLR [13, 14], thermal effect from solution dispersions can also contribute to NLR under continuous wave or long pulse laser. For GO sheets in dispersions, free carriers, π electrons and bound electrons of sp^2 domains and sp^3 matrix can contribute to the NLR. Reorientation effects of the GO sheets and thermal effect should be considered according to the duration of pulse.

Moreover, unlike the case of single layer or few-layer graphene on a substrate, the NLR response and $n_{2\text{eff}}$ value of graphene sheet or GO sheets dispersions is the sum of NLR signals from a large amount of sheets interacting with laser pulse. The NLR response or $n_{2\text{eff}}$ value of single graphene sheet or GO sheet cannot be obtained accurately, only can be obtained by

roughly qualitative estimation [13], because the sheets are dispersed and the sheets sizes are not uniform. So the values of $n_{2\text{eff}}$ (or n_2) in the three cases, cannot be compared directly, because the duration of laser pulse and wavelength, the samples and the mechanisms contributing to NLR are different.

4. Conclusions

In summary, the NLR properties of GO in DMF were studied in nanosecond, picosecond and femtosecond time regimes by Z-scan technique, NLA properties related to NLR properties were also studied. Results show that the dispersion of GO in DMF exhibit negative NLR properties, which is mainly attributed to transient thermal effect in nanosecond time regime. GO dispersions also exhibits negative NLR in picosecond and femtosecond time regime, which may be mainly arising from electronic polarization and possible free carrier refraction of sp^2 domains and sp^3 matrix of GO sheets. GO dispersions and GO sheets keep negative NLR behaviors although the SA behaviors to RSA transition as pulse energy (intensity) increases in nanosecond, picosecond and femtosecond regimes, this makes GO materials promising candidates for practical applications as broadband and broad domain saturable absorbers, optical switching and optical limiter.

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